



# **Modeling & Uncertainty Quantification of Electronic Devices within Radiation Environments**

## **Qualification Alternatives to the Sandia Pulse Reactor (QASPR)**

**Tech Talk – University of Wisconsin Madison  
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**Joseph Castro**  
**Qualification/Requirements PRT Lead**  
**Electrical & Microsystem Modeling, Org. 01437**



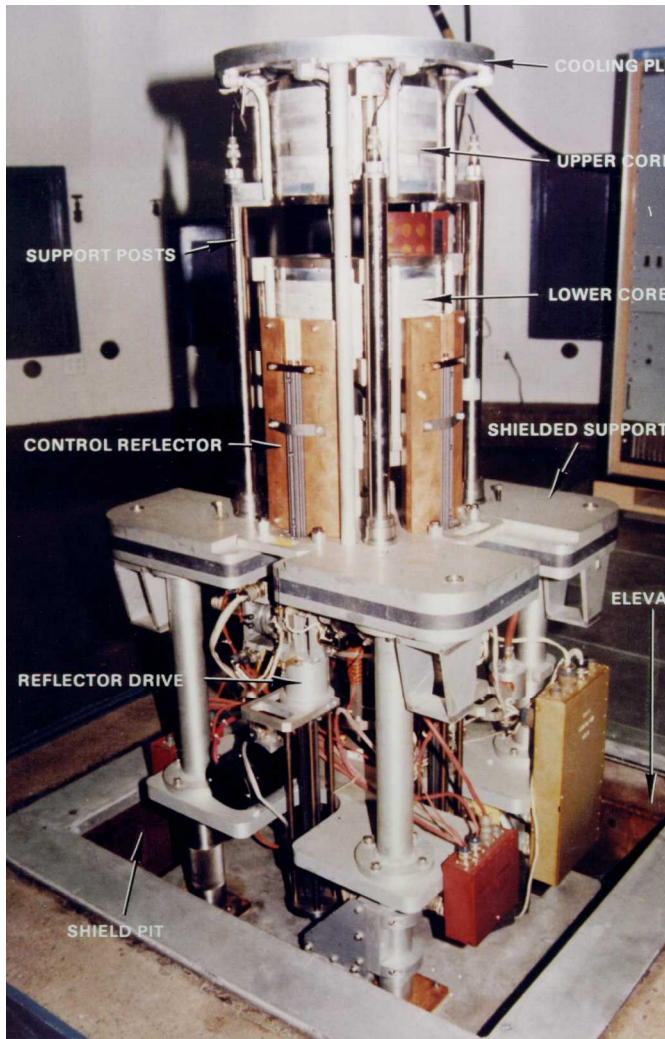
# Overview Of Topics

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- I. What is QASPR?**
- II. QASPR Approach**
- III. Identifying & Quantifying Uncertainties**
- IV. Propagating Uncertainty**
- V. Best Estimate + Uncertainty**
- VI. Conclusion**

# **Need:** Qualify electronics for intense neutron bursts without a fast-burst reactor – $\mu\text{s}$ time scales

## **SPR-III pulse reactor**



### **Features:**

$5 \times 10^{14} \text{ n}^0/\text{cm}^2$  in  $76 \mu\text{s}$   
(1-MeV Si equivalent)  
within 17-cm cavity

### **Status:**

Permanent shut-down  
in September 2006  
per DOE policy on  
special nuclear materials

# Short pulse neutron environments create damage in materials and devices

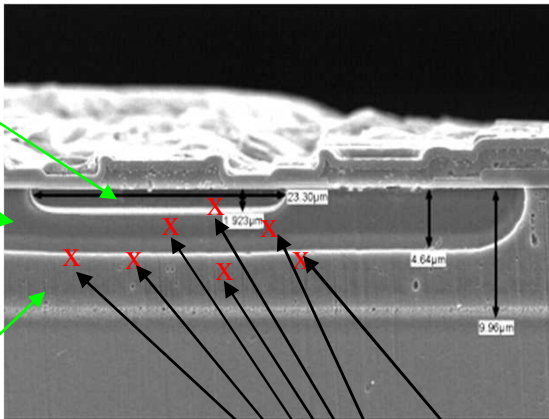
Requirements drive the need to qualify devices and systems

Neutrons create displacement damage

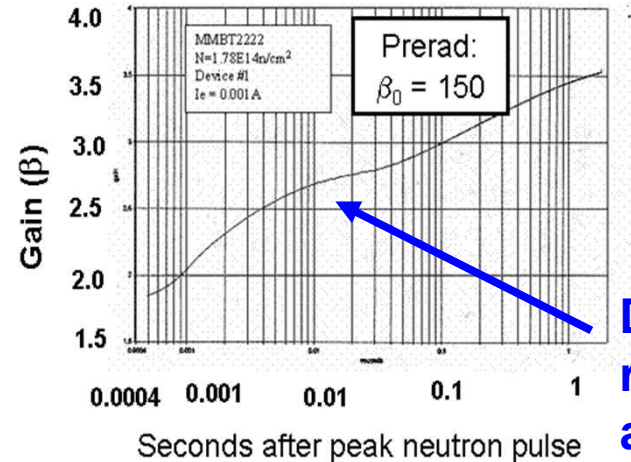
Emitter  
(n-type)

Base  
(p-type)

Collector  
(n-type)



Displacement  
damage  
degrades  
device gain.

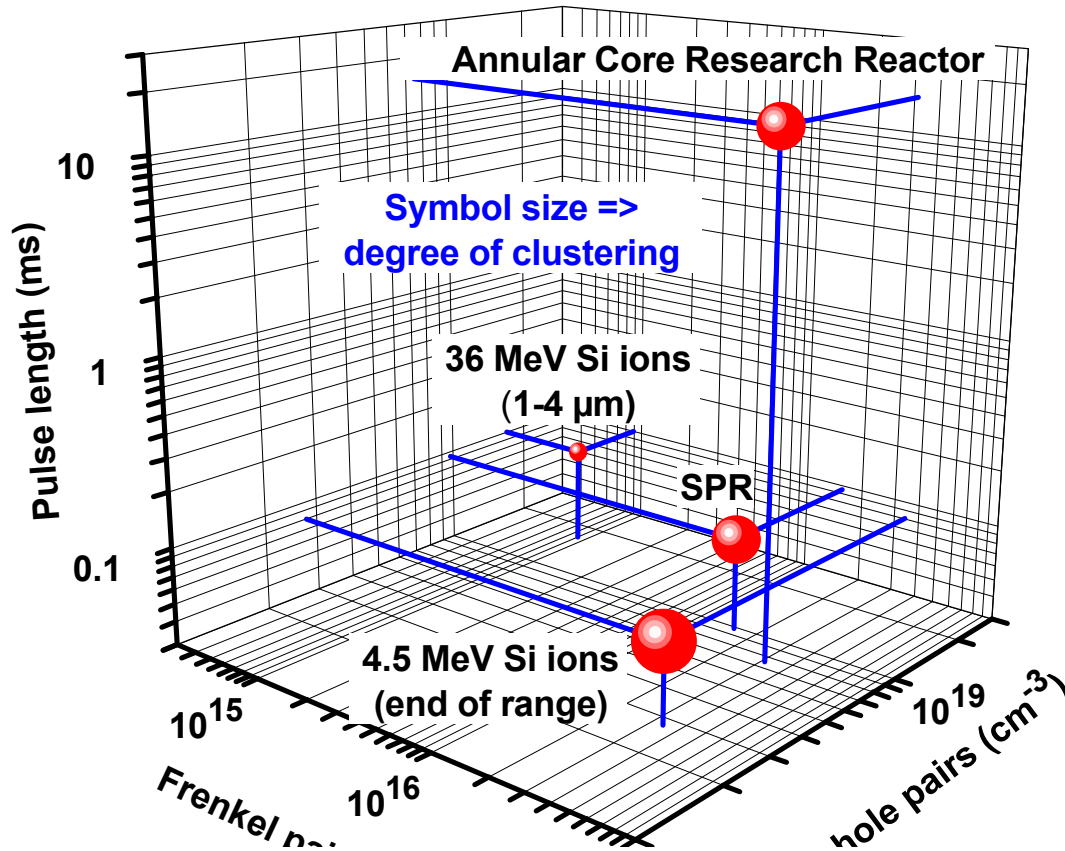


Damage  
recovery  
annealing

# **Solution:** The QASPR approach

## Merging Experiments, Modeling, and UQ

### I. Irradiation testing in alternative facilities still available



### II. Science-based modeling to go from tests to response

Neutron (& gamma) production  
SPR, IBL, ACRR, etc.



Transport of radiation particles



Defect production & ionization  
in electronic materials



Time evolution of defects



Carrier behavior  
and resultant device operation

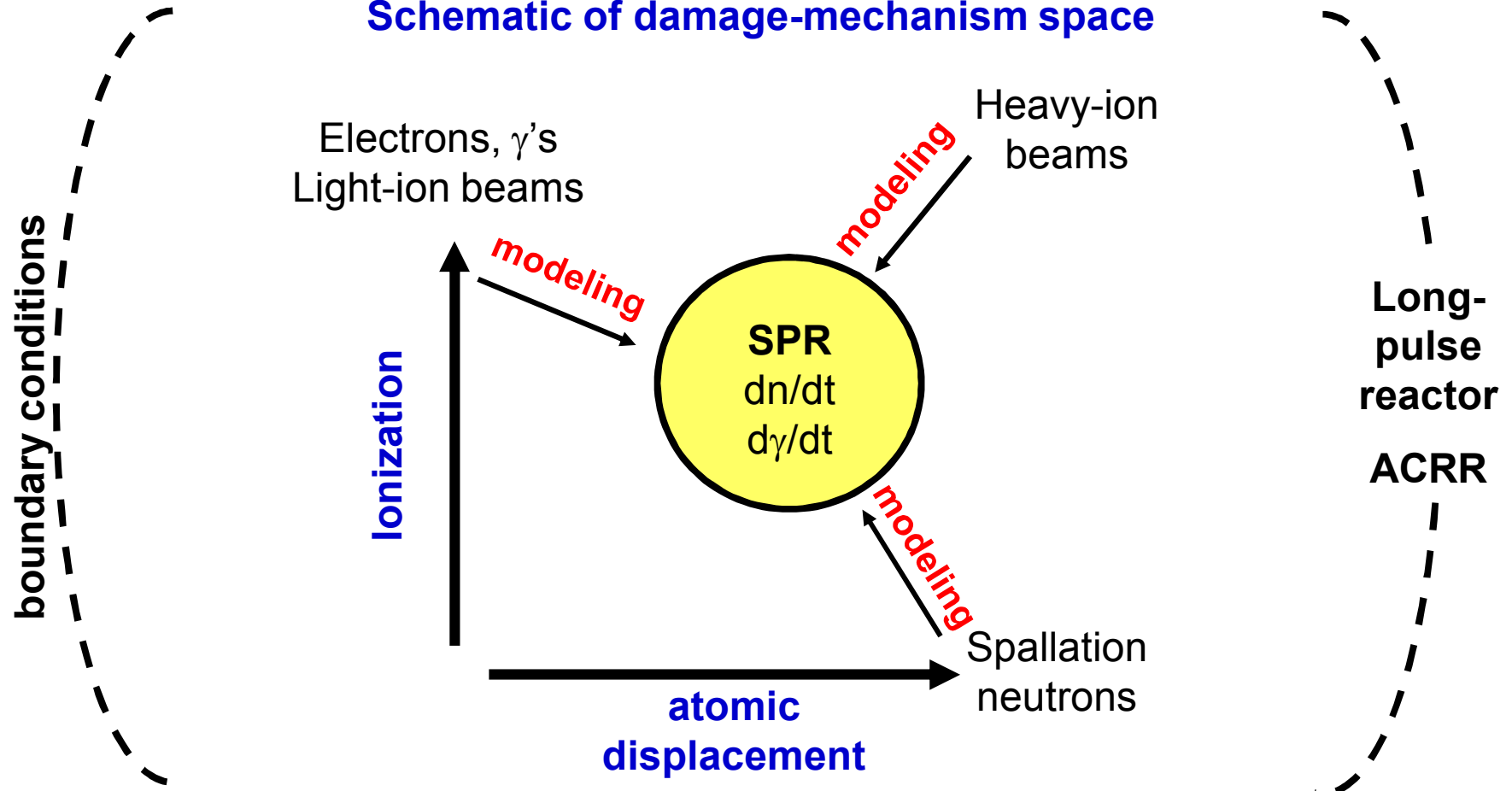


Circuit operation

### III. Quantify uncertainty in simulation and experiment – make quantified comparisons

# Augment testing at alternative facilities with computational modeling & uncertainty quantification

## Schematic of damage-mechanism space





# UQ-Relevant Terms

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- **Calibration:**
  - Use existing test data (model development) to improve physics model parameter settings in simulation code.
- **Validation:**
  - Assess agreement between simulation data and new test data (validation).
    - *Not using same test data from calibration.*
- **Uncertainty quantification:**
  - Estimate uncertainty in test data.
  - Propagate input parameter uncertainty through code(s), and estimate uncertainty in simulation data.
- **Related topic – Verification:**
  - Assess mathematical correctness of simulation code(s).





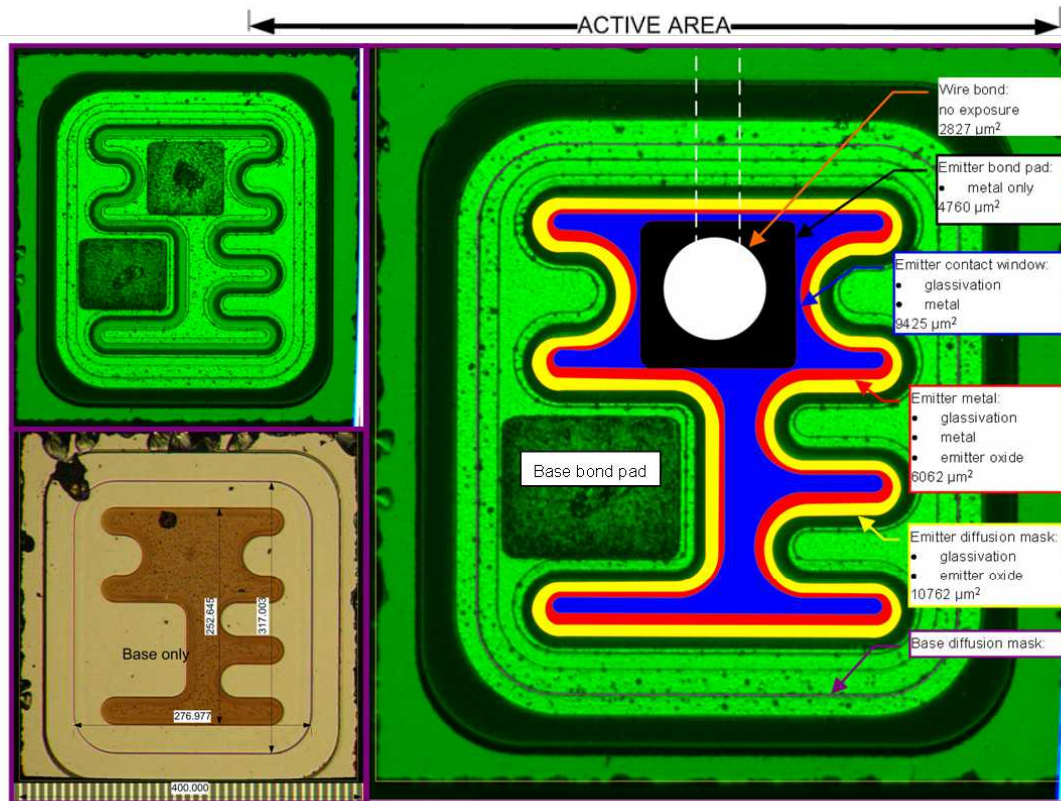
# Categories of Uncertainty

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- **Physics parameters**
  - cross-sections
  - diffusion parameters
- **Device model**
  - doping characteristics
  - device areas
- **Device performance (electrical) measurements**
  - current measurements
- **Radiation environments**
  - Ni activity
  - Si calorimeter integral data
- **Model form (fidelity)**
  - Psuedo-1D Charon vs. 2D Charon
  - Oxide
- **Numerical/computational**
  - not varying since small compared to other uncertainties



# Device Characterization Uncertainty



Optical die photos of a BJT (Fairchild MMBT2222A) used to measure various features. This information is used to target areas for SIMS and SRP analysis, provide scaling factors for device modeling, and for ion beam irradiation experiments. Linear accuracy is 2%; area accuracy is 4%. Care is taken to avoid digital photo distortion.

Top left: As received die.

Bottom left: Die that has been deprocessed (unlayered) to bare silicon and junction stained. Brown area is the emitter diffusion. Scale at bottom is a NIST standard ( $\mu\text{m}$  units)

Right: Die map of different regions that lie over the emitter diffusion. The areas are identified by their outer borders. Interpretation of ion beam irradiation experiments using device models require measurement of the area for each combination of glassivation, metallization, and thermal oxide layers present over emitter diffused portion of this device.

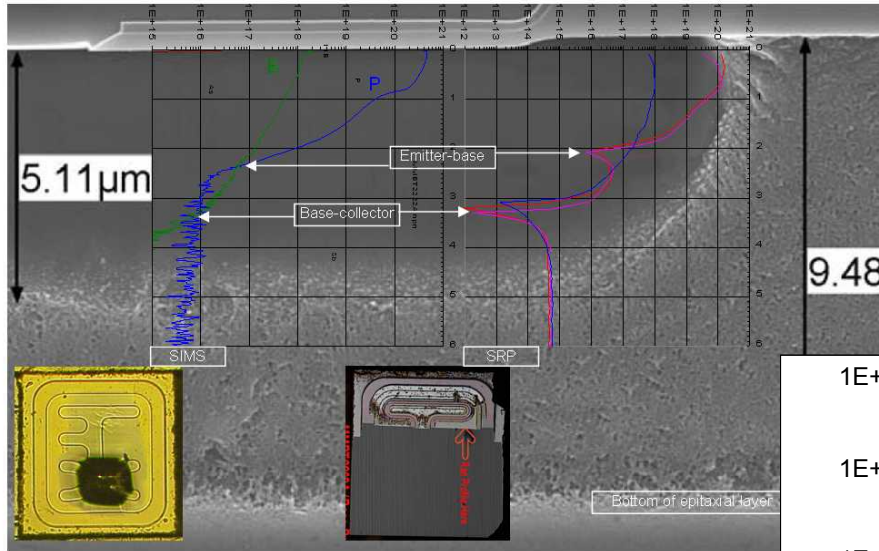
**Scanning Electron  
Microscope  
measurements of  
dimensions ~5%  
uncertainty**

Microsemi 2N2222A [npn](#)

**Area measurements  
using optical die  
have ~4%  
uncertainty**

layer thickness features.  
is taken to avoid effects  
tive diffusions; the layers'  
stratation depths when

# Dopant measurements have 20% uncertainty



Secondary ion mass spectroscopy (SIMS) and spreading resistance (SRP) for Fairchild MMBT2222A npn superimposed on junction stained cross section. In this case the base-collector junction depths from SIMS are shallower than the junction stain (5.11 μm), which is an indicator only.

Left plot: SIMS metallurgical base-collector junction depth (3.40 μm) from dopant (P, B) concentrations

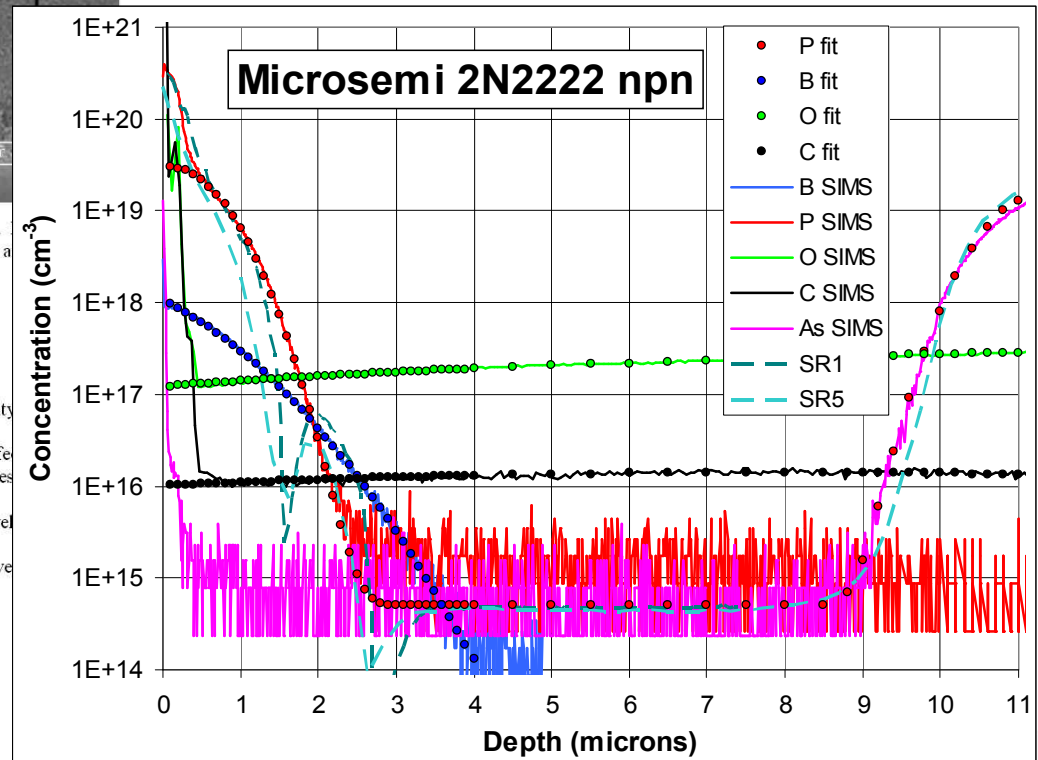
Absolute concentration accuracy = 40%; depth scale accuracy = 5% (crater profilometry) ~ 0.15 μm

Right plot: SRP electrical base-collector junction depth (3.25 μm) from free charge carrier concentrations

Absolute concentration accuracy = 20%; depth scale accuracy = 3% (bevel angle)

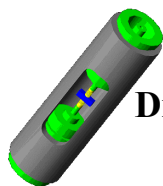
Note SIMS / SRP accuracies are affected by:

1. Dopant type (SIMS ion implanted standard used, mass interference, signal to noise / SRP carrier density carrier mobilities for P and B doped Si, even when other dopants are present)
2. Dopant /carrier concentration gradient with depth (SIMS sputter rate variations / SRP space charge effects higher doped, sharp junctions (emitter-base) are more precise than lower doped, more Gaussian profiles ones (e.g. base-collector))
3. Size of the measured feature (SIMS signal to noise and raster alignment with small features / SRP bevel required and feature edge effects). Minimum size: SIMS ~ 40 μm, SRP ~ 25 μm width.
4. Sample topology. Small steps in Si surface at edge of diffusions from device processing. Possible over to limitations of selective etches used for deprocessing prior to analysis. Corrections can be applied.



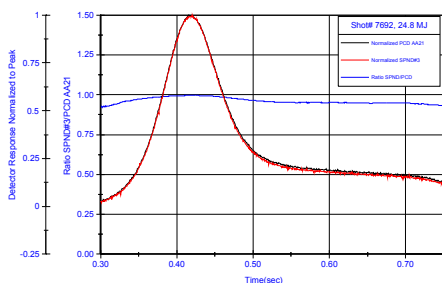
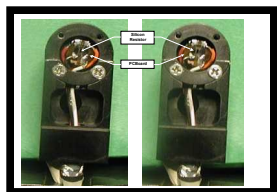
# Improvements in dosimetry/analysis support for uncertainty characterization for QASPR

## Time Profile



Diamond PCD

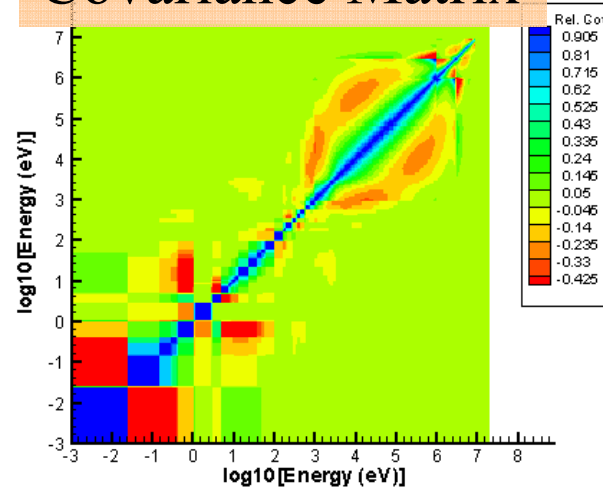
New Si calorimeter



Uncertainty estimate  
200%  $\rightarrow$  25%

## Spectrum

### Covariance Matrix

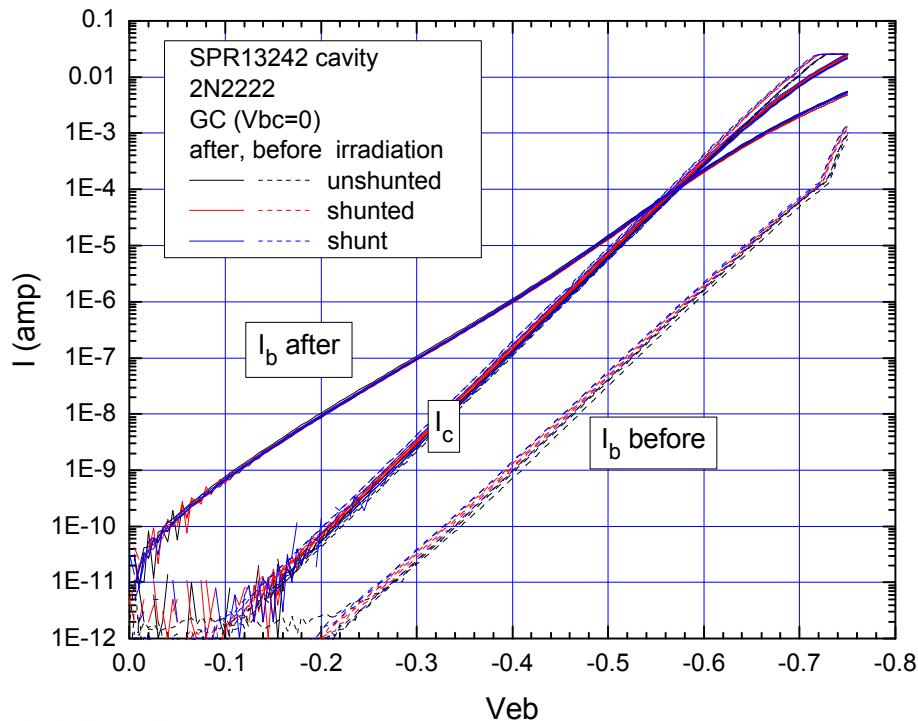


Uncertainty estimate  
 $\sim 5\%$

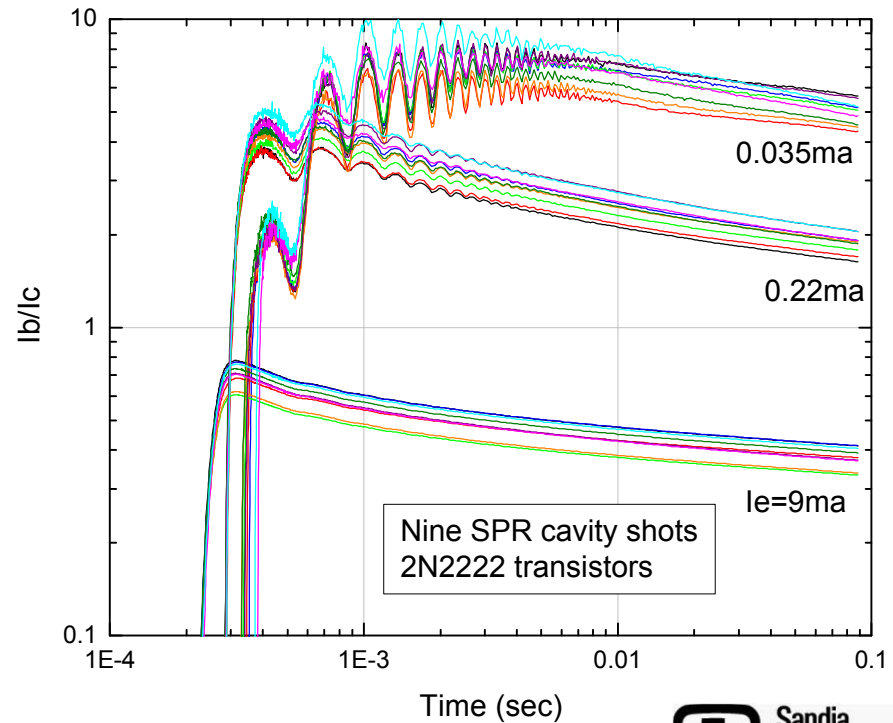
# Radiation Test (Experimental) Data

Test data consists of time resolved voltage & current during & after irradiation and pre & post measurement of IV characteristics or Gummel curves.

Gummel curves



Inverse gain vs time

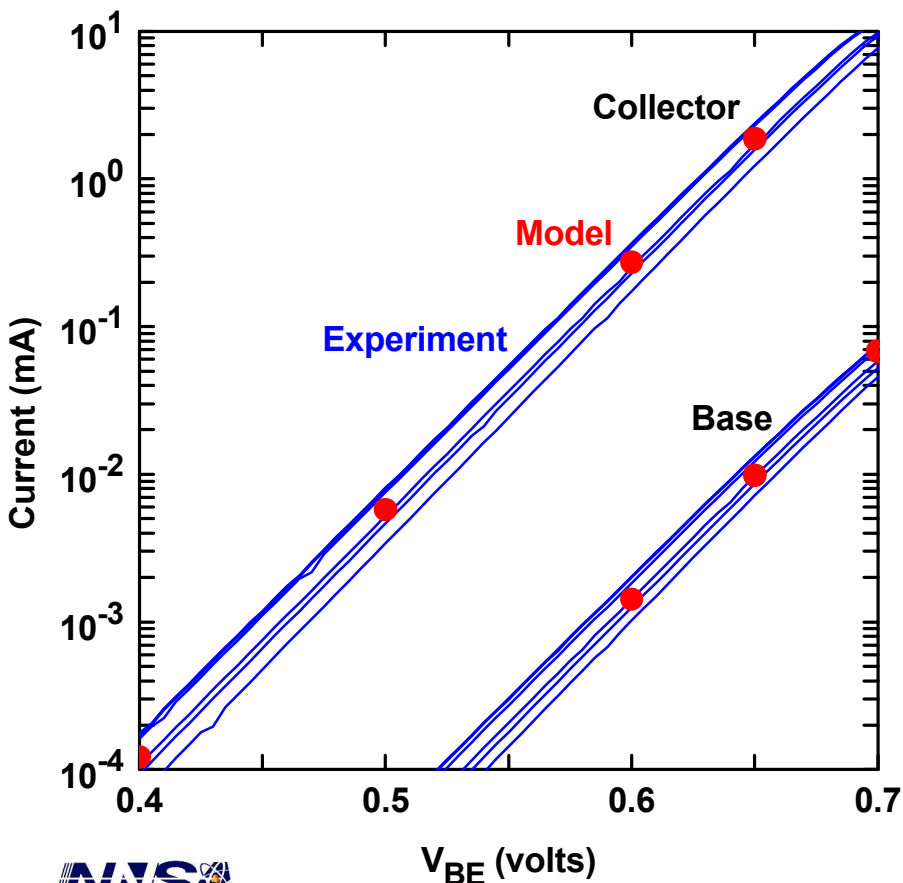




# Experimental variability & uncertainty are important in UQ

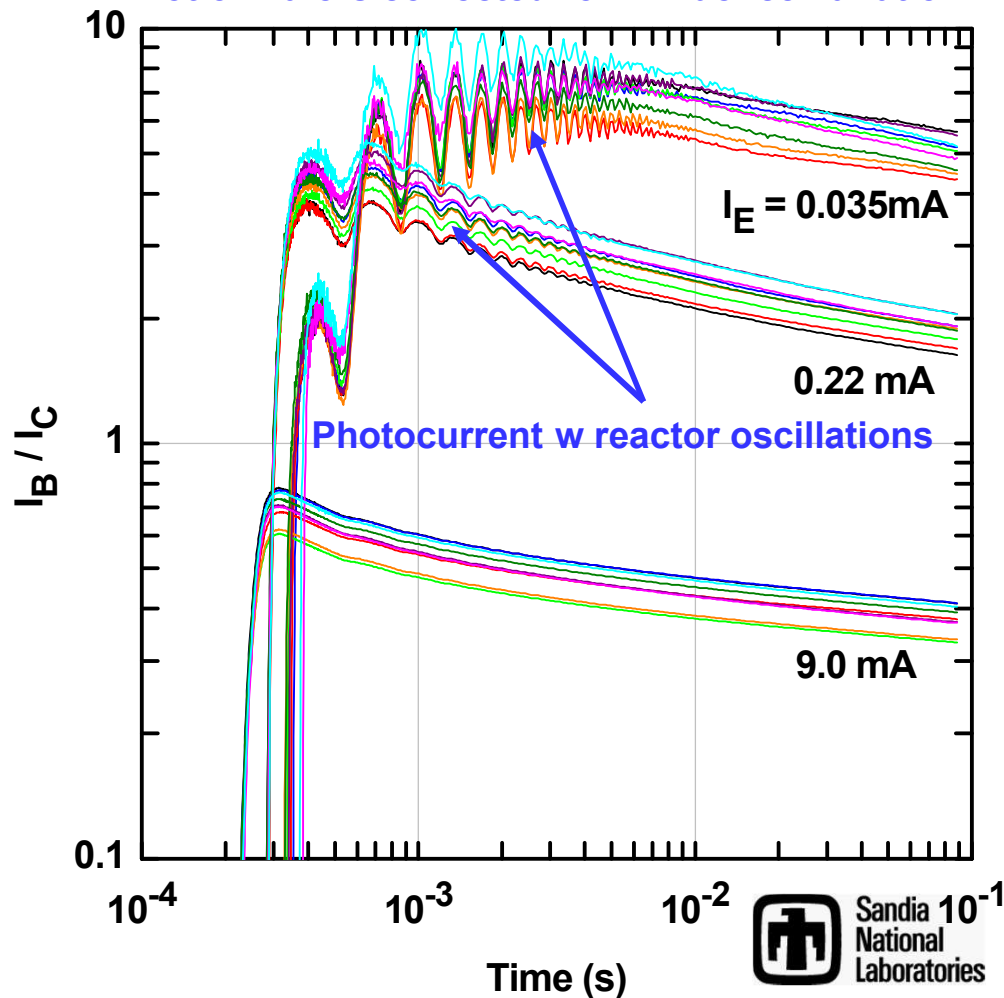
## Device-to-Device

Pre-rad Gummels of 7 n-p-n BJTs  
Single wafer



## Shot-to-Shot

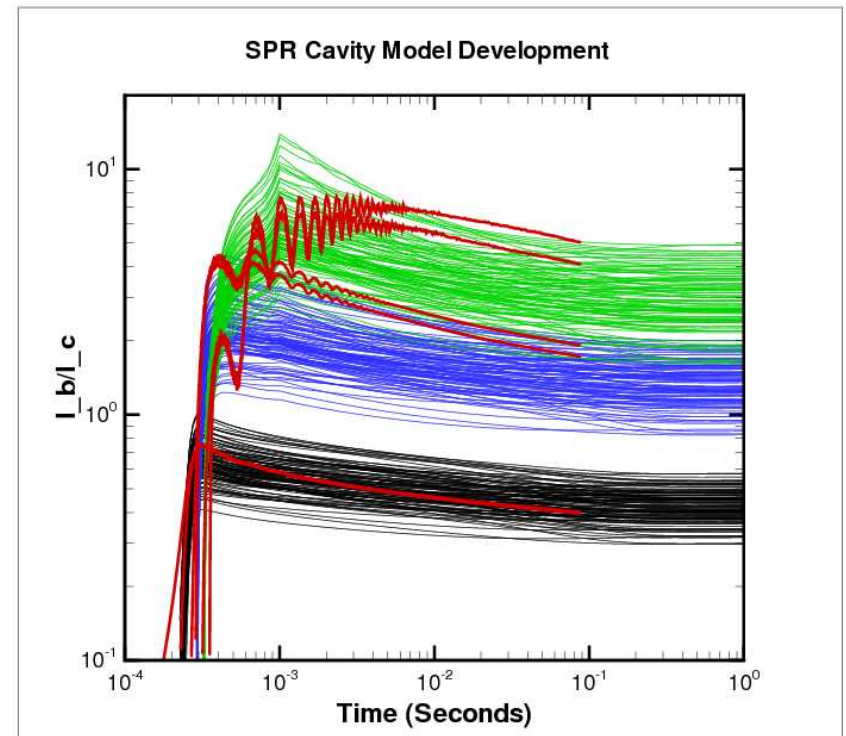
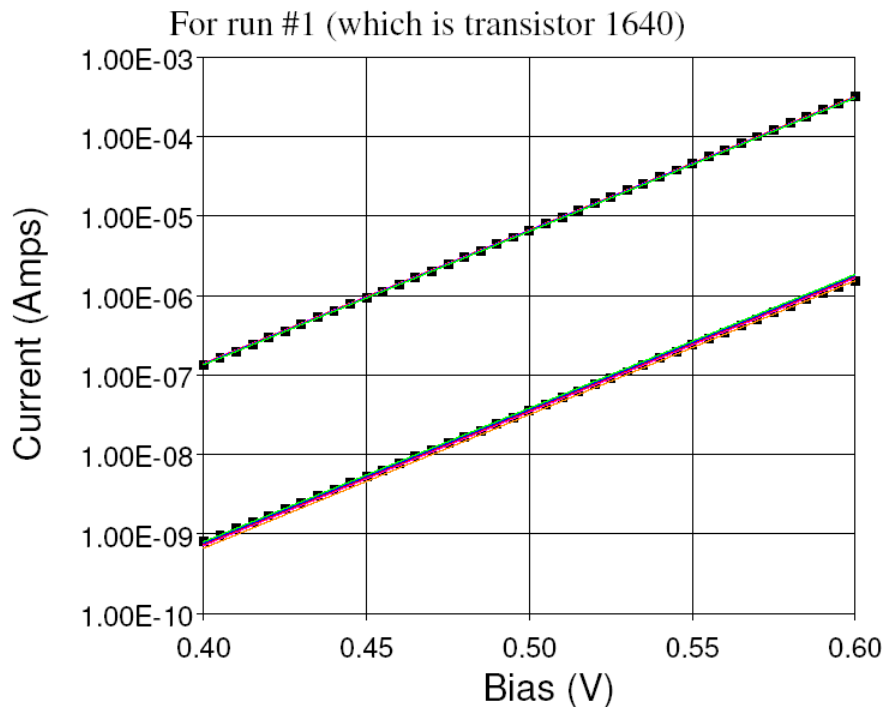
9 SPR-cavity shots w 3 n-p-n BJTs/shot Single  
lot of wafers corrected for  $n^0$  fluence variation



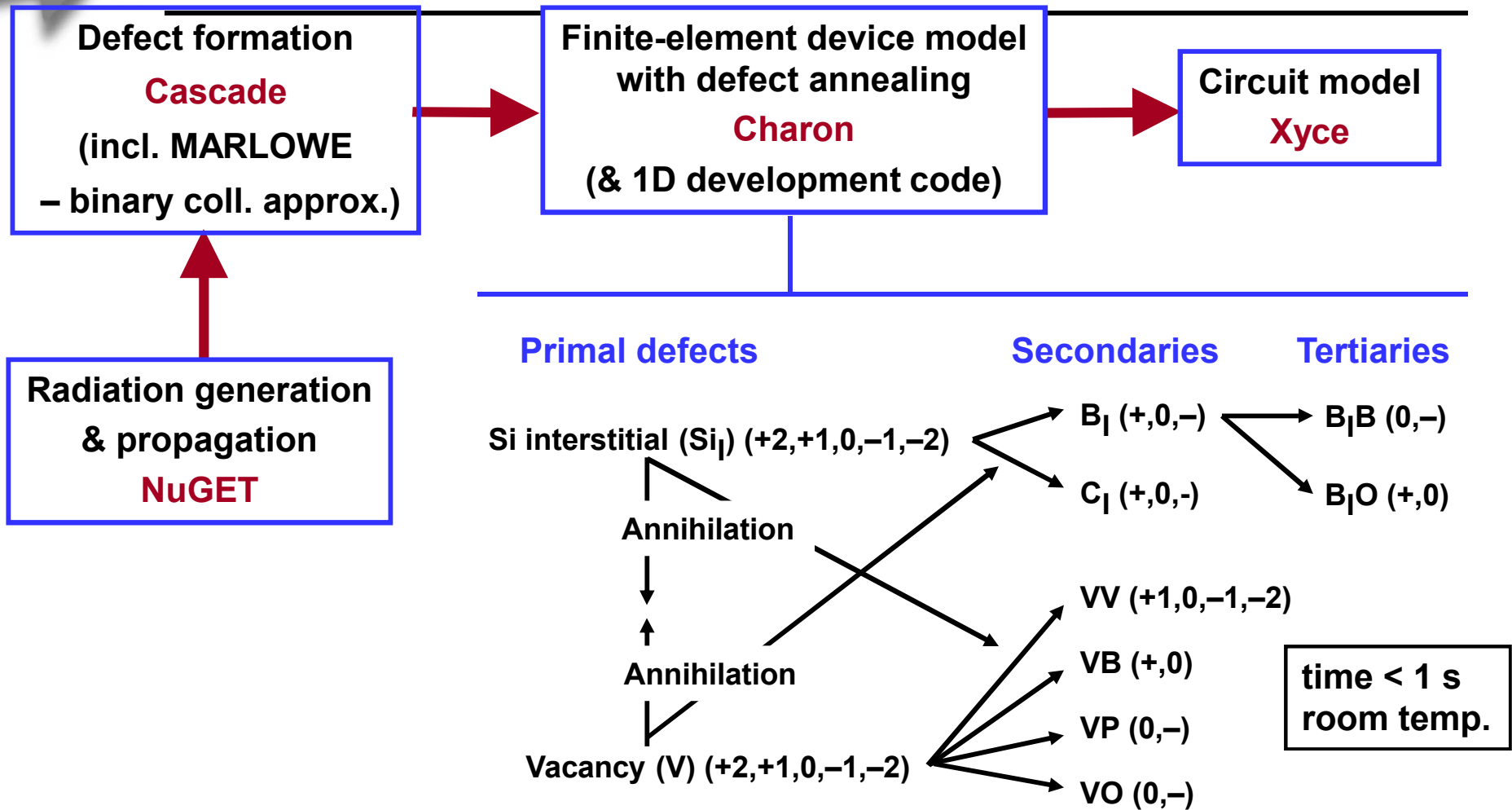
# Uncertainty is Being Reduced through Calibration

- Dopant profile uncertainty
  - Unirradiated operating performance measured
  - Models run to optimize fit to measured performance by adjusting dopant profiles

- Physics parameters uncertainty
  - Irradiated operating performance measured
  - Model runs to optimize fit to transient performance by adjusting poorly known physics parameters



# Codes in primary computational sequence



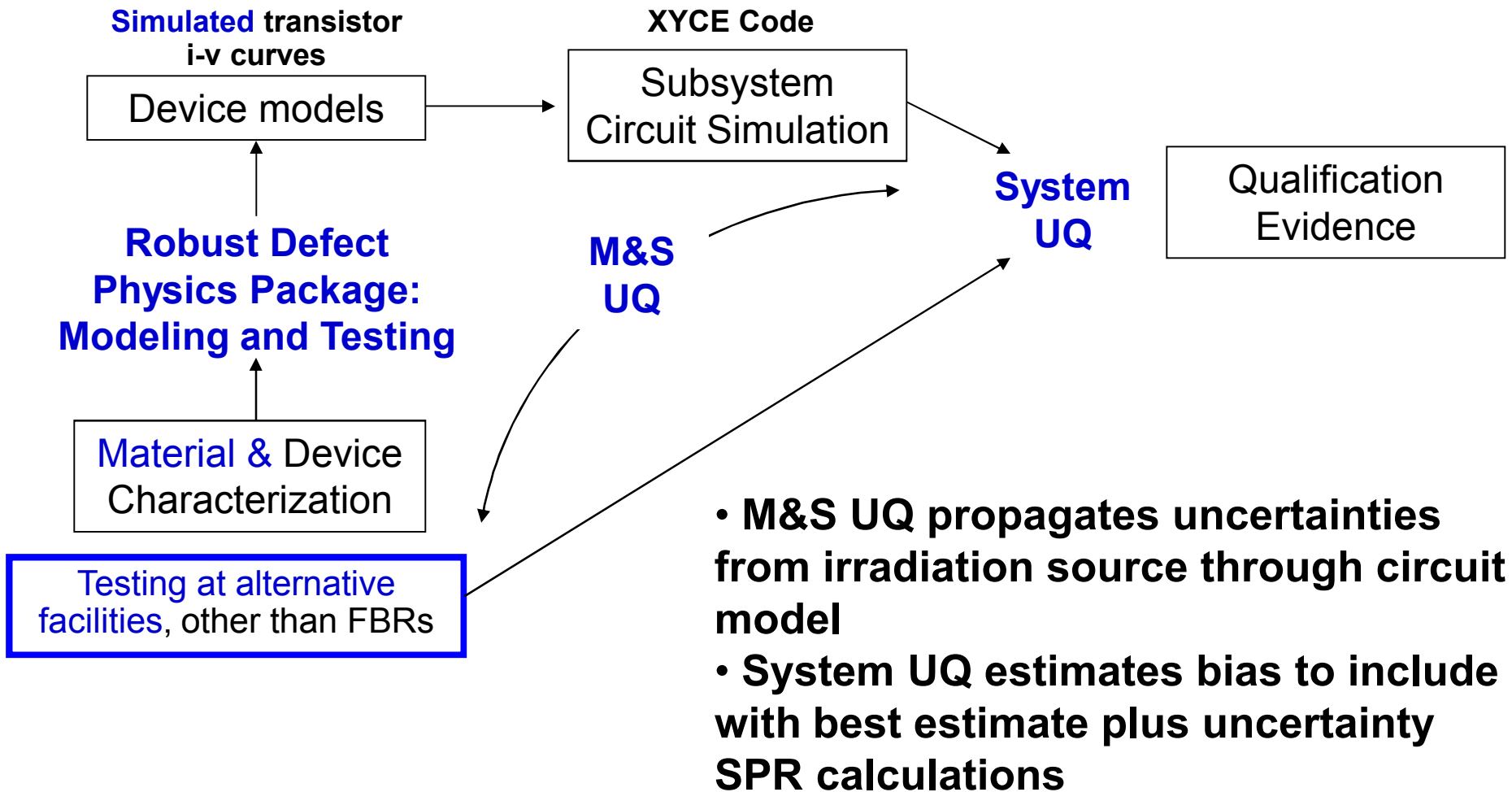
## Defect-physics approach:

Use defect species well founded on experiment or *ab-initio* theory

Adjust poorly known physics parameters for consistency with testing



# The QASPR qualification approach will include device testing and device/subsystem modeling





# Propagating Uncertainty

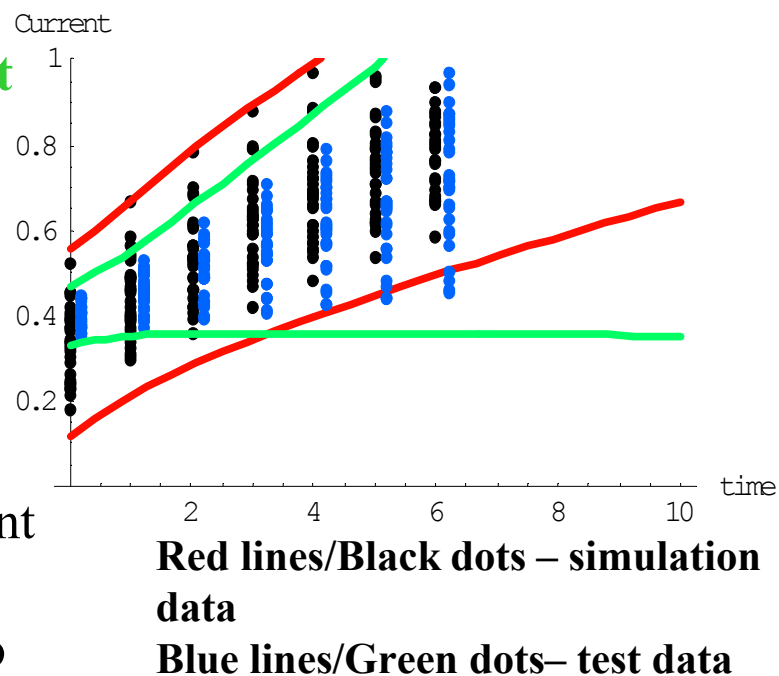
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- On the order of 150-200 uncertain parameters throughout QASPR for device (those that have been identified)
- We cannot “blindly” propagate uncertainty for all parameters
  - setting conservative bounds on all variables may produce meaningless results
  - limited by time and budget
- Limit the number variables based on reduction rationale
  - sensitivities of parameters
  - strong correlations between parameters
  - reduction of bounds with calibration
  - some expert judgment – will be formalized with sensitivity analyses

# End Game: Best Estimate + Uncertainty

## Device Process

- Characterize as-built device parameters and conduct unirradiated testing (**Experiment**)
- Calculate unirradiated device operating performance to finalize device model (**Modeling**)
- **Conduct device performance experiments at alternate facilities (Experiment)**
- **Predict device performance at alternate facilities (Modeling)**
- Use device computational and experimental results to determine any systematic bias in modeling (**UQ**)
- Predict device performance in SPR environment (**UQ+Modeling**)
- Adjust SPR prediction using systematic bias to construct best estimate plus uncertainty (**UQ**)





# Conclusion

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- **QASPR integrates a wide range of modeling and experiments with UQ to provide a best estimate + uncertainty of electrical device/circuit response within a radiation environment**
- **This effort spans eight Sandia centers and exemplifies a trend toward inter-organizational integration in pursuit of larger objectives.**



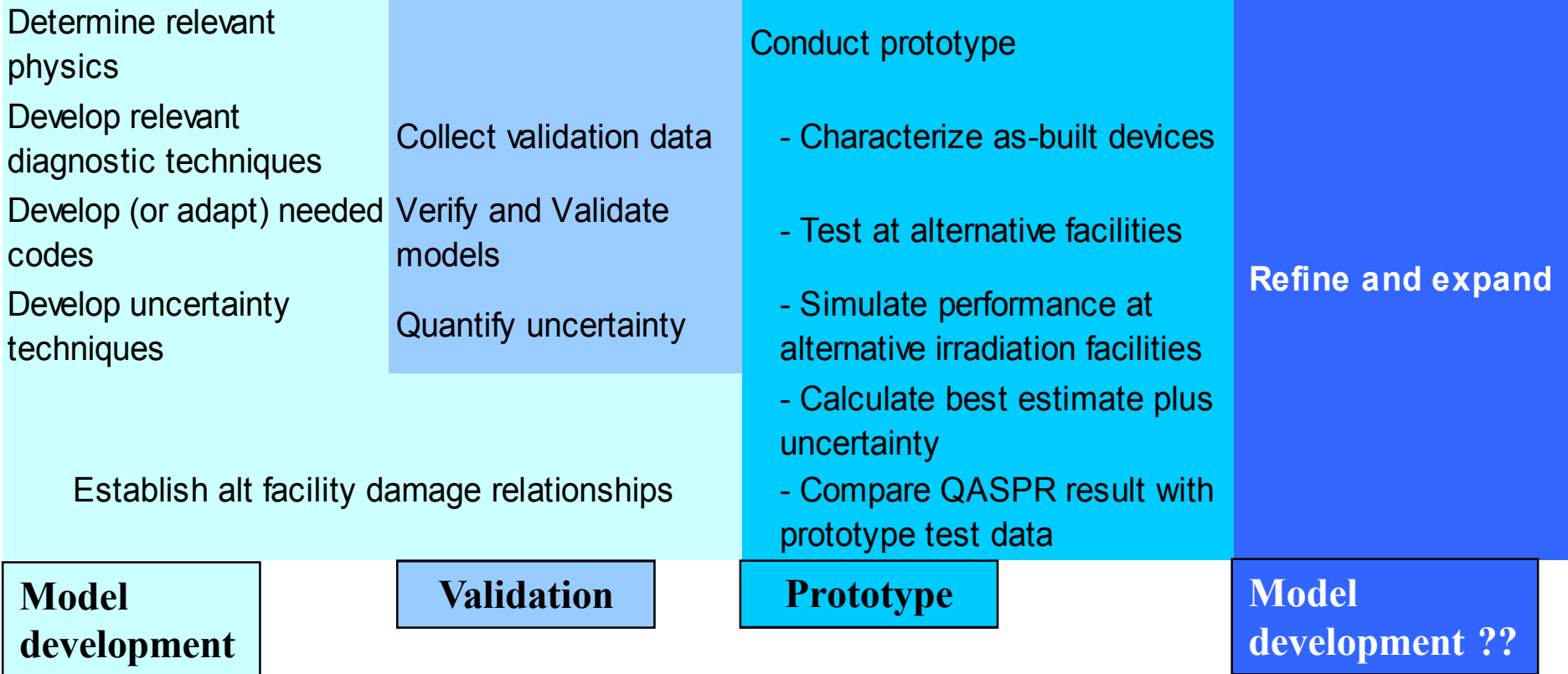
# Supplementary Slides

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# The QASPR development plan requires different types of data to be collected

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Data Types